

SUBSTRATE CARRYING DEVICE AND SUBSTRATE PROCESSING DEVICE

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Inventor(s): SUZUKI SATOSHI; KISE KAZUO
Applicant(s): DAINIPPON SCREEN MFG CO LTD
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Abstract

PROBLEM TO BE SOLVED: To prevent the downward deflection of a substrate in the carrying of a large-sized substrate and the stay of a processing fluid thereby by setting the height of the substrate surface of an intermediate support means larger than the substrate support surface of an end part support means.

SOLUTION: A substrate W is carried while both end lower surfaces are supported by an end support rollers 20 of a substrate carrying device 11, and the center lower surface is supported by an intermediate support roller 21 thereof. Since the support surface height H2 of the intermediate support roller 21 is set larger than the support surface height H1 of the end support rollers 20, the substrate W is carried in the mountain-shaped deflected state as that the center part is the highest, and the height is reduced toward both the sides. Thus, even if a wash water is supplied to the surface of the substrate W, the wash water is smoothly carried from the substrate center part toward both the outer sides, and can be prevented from being stayed on the substrate surface. Thus, the whole substrate surface can be uniformly cleaned.

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